

Multilayer Optics for X-Ray Diffractometry



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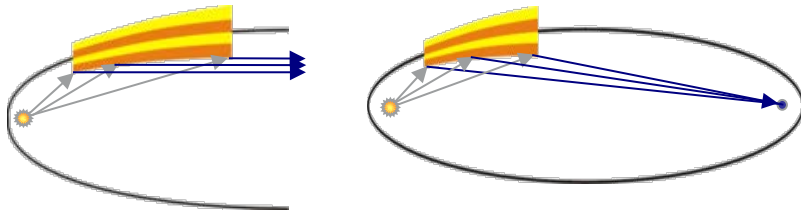
1. Multilayer Optics – Design and Fabrication

2. XRD-Applications with Multilayer Optics

3. The Past and the Future

Multilayer X-ray Optics for specific applications

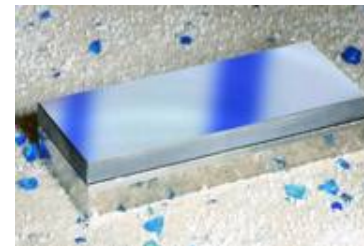
Diffractometry



1-dimensional

Göbel Mirror
Gutman Optics

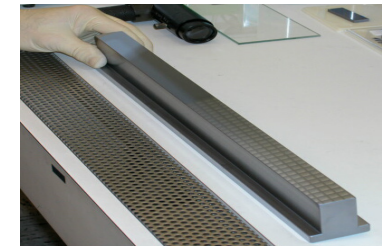
Spectrometry



Plane / Curved

WDXRF -
Multilayer
Analyser

Others

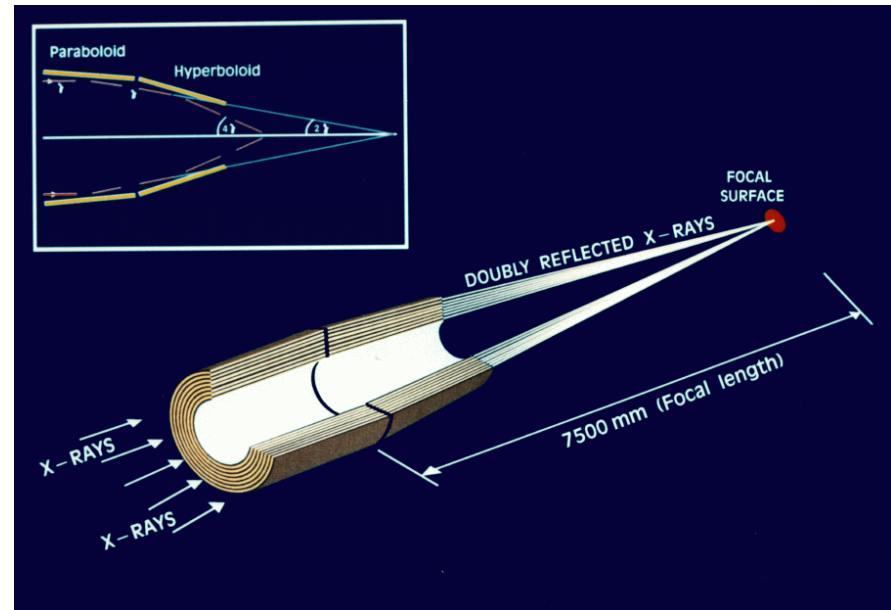


different types

Synchrotron
EUV lithography
X-ray
microscopy
Medical
equipment
X-ray astronomy

NuSTAR Spectroscopic Telescope Array

- 6 – 79 keV
- Pt/SiC and W/Si coating
- Shells spaced apart by graphite, held together by epoxy



<http://www.nustar.caltech.edu/about-nustar/instrumentation/optics>

Substrate :

- Roughness
- Curvature (or plane)
in one or two dimensions

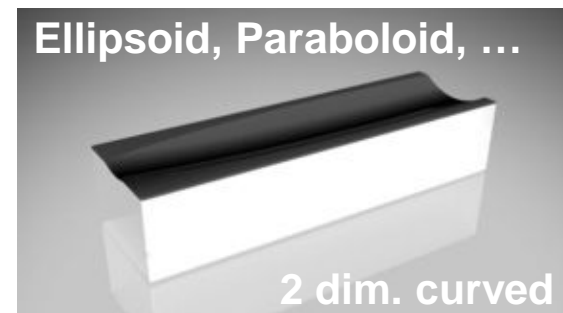
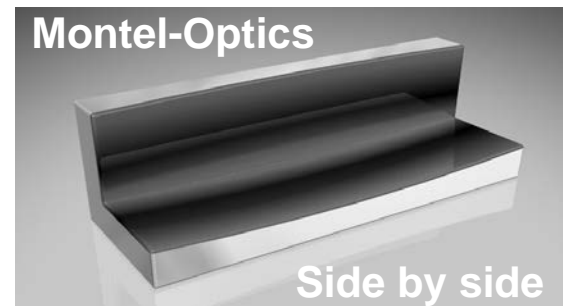
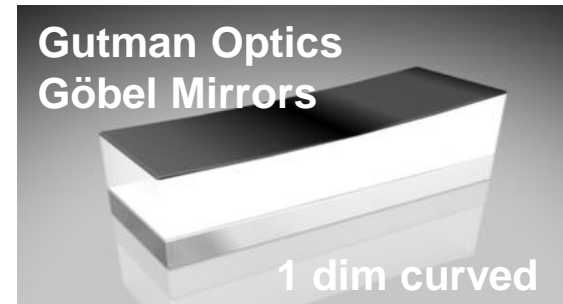
Multilayer film:

- Materials
- Layer Thickness
- Gradients (lateral and depth)

Mounting:

- combination of several multilayers

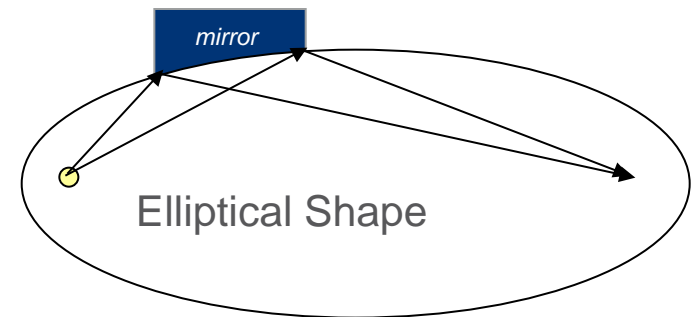
1 arcsec = $1/3600$ deg = 0.00485 mrad;
for comparison: Bragg peak widths ~ 100 – 200 arcsec



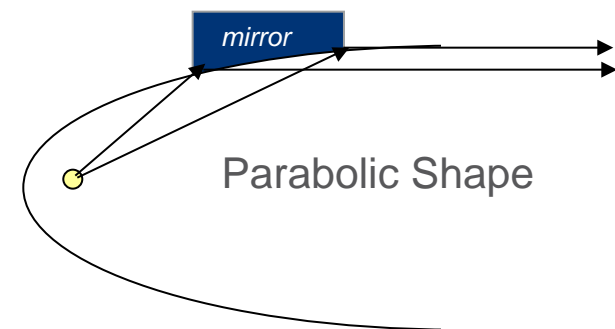
Material: Si, fused silica, quartz, zerodur, ...

Properties:

- prefigured or “curved and glued” wafers with
- low roughness ($< 3 \text{ \AA}$ down to 1 \AA)
- curved with radii of several meters in beam direction plus several mm curvature for ellipsoids, paraboloids, ...
- peak to valley: up to several $100 \mu\text{m}$
- length in lab instruments up to 15 cm
- optimum shape: slope errors down to 5 arcsec (curved and glued), down to 0.03 arcsec (prefigured)



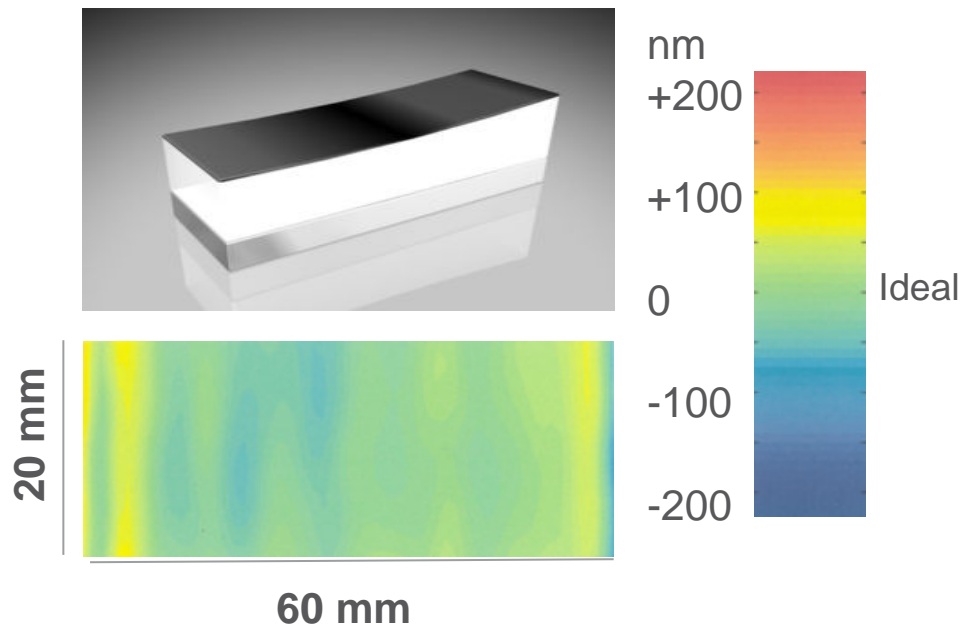
Source



Source

Method: profilometry (e.g. Laser-Interferometry)

Example: 1-dim parabolic mirror



Shape as specified with
errors up to ± 100 nm

Slope error:

horizontal 3.3 arcsec rms

vertical 0.5 arcsec rms

■ Typical Parameters

■ Reflected Photons:

λ : 0.01...40 nm / E: 30 eV ... 100 keV

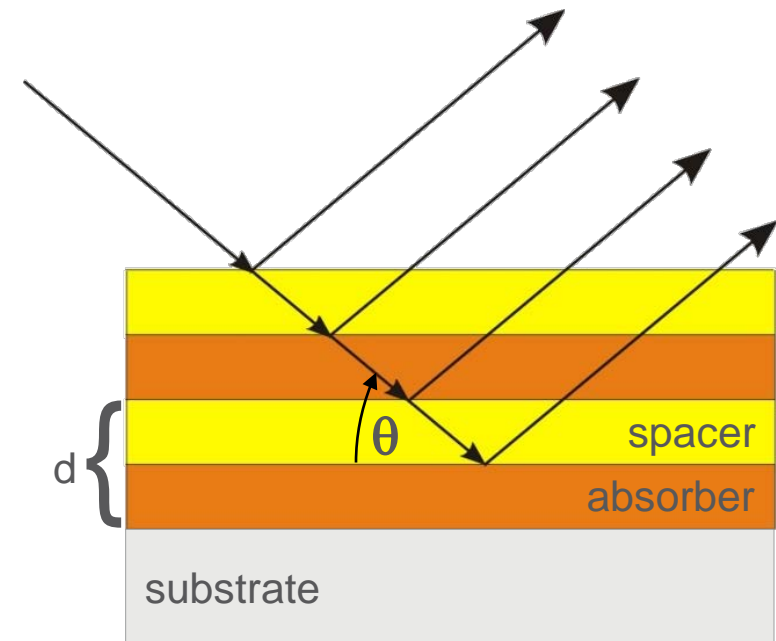
■ d: 1...30 nm

■ θ : 0 – 90 °

■ N: 40...1000 (Number of Pairs)

■ Γ -Ratio: 0.1...0.8 (d_{absorber}/d)

■ Lengths: 0.15 m (lab)...1.5 m (synchr)



δ : Dispersion of Materials

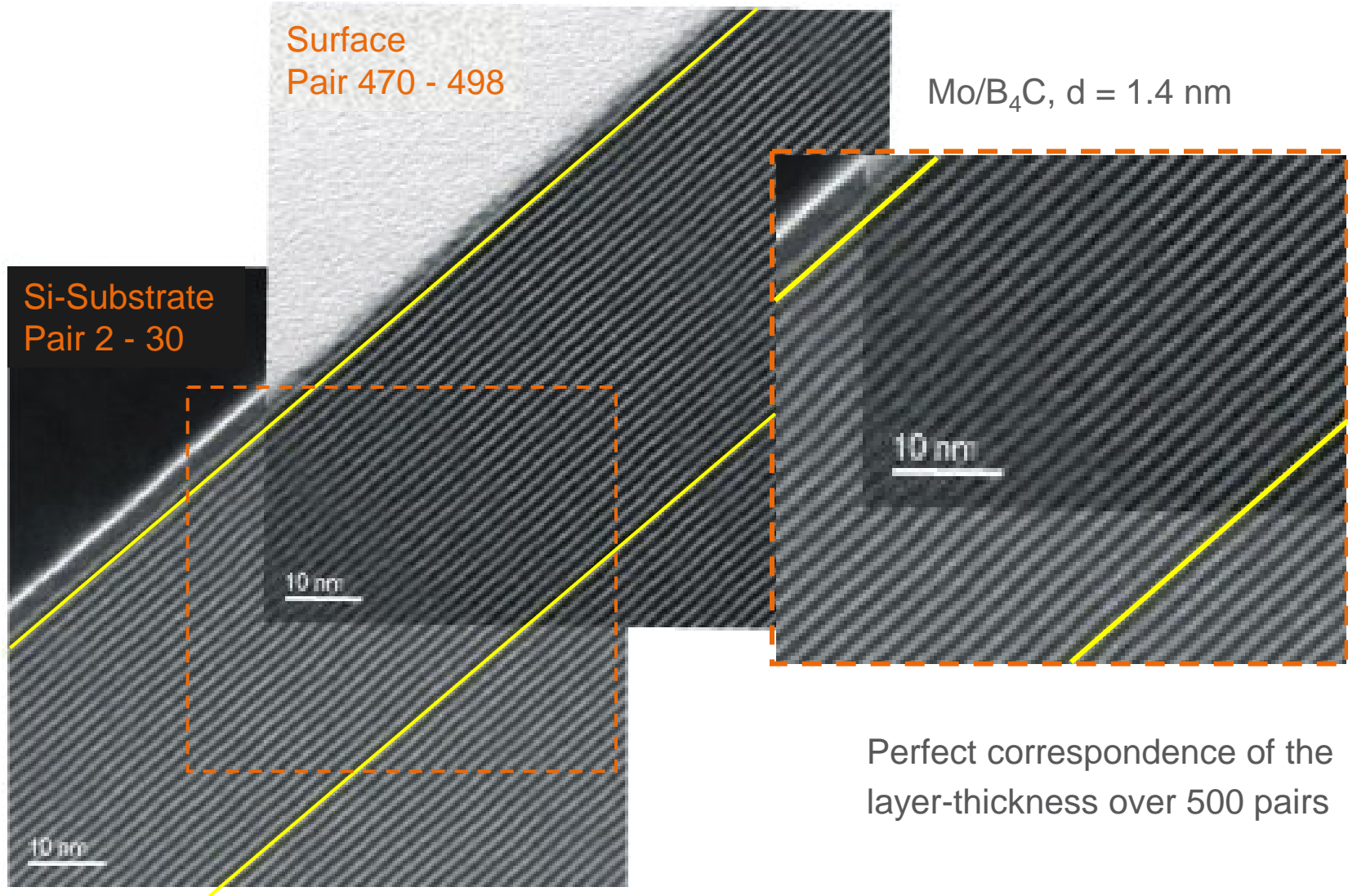
$$n\lambda = 2d\sin\vartheta \cdot \sqrt{1 - \frac{2\delta - \delta^2}{\sin^2\vartheta}}$$

- **area for deposition:**
up to 150 x 12 cm or 8" diameter
- **lateral gradients by substrate moving**
- **Target materials:**
absorber:
W, WSi₂, Ru, V, La, Mo, TiO₂, Ni ...
spacer: C, BN, B₄C, Si,...
- **precision:**
typical $\pm 1\%$, up to $\pm 0.2\%$
- **Difference of deposition facilities:**
sizes, gradients and precision



TEM-Picture of a multilayer coating

Measured by Prof. Jäger et al., Univ. of Kiel

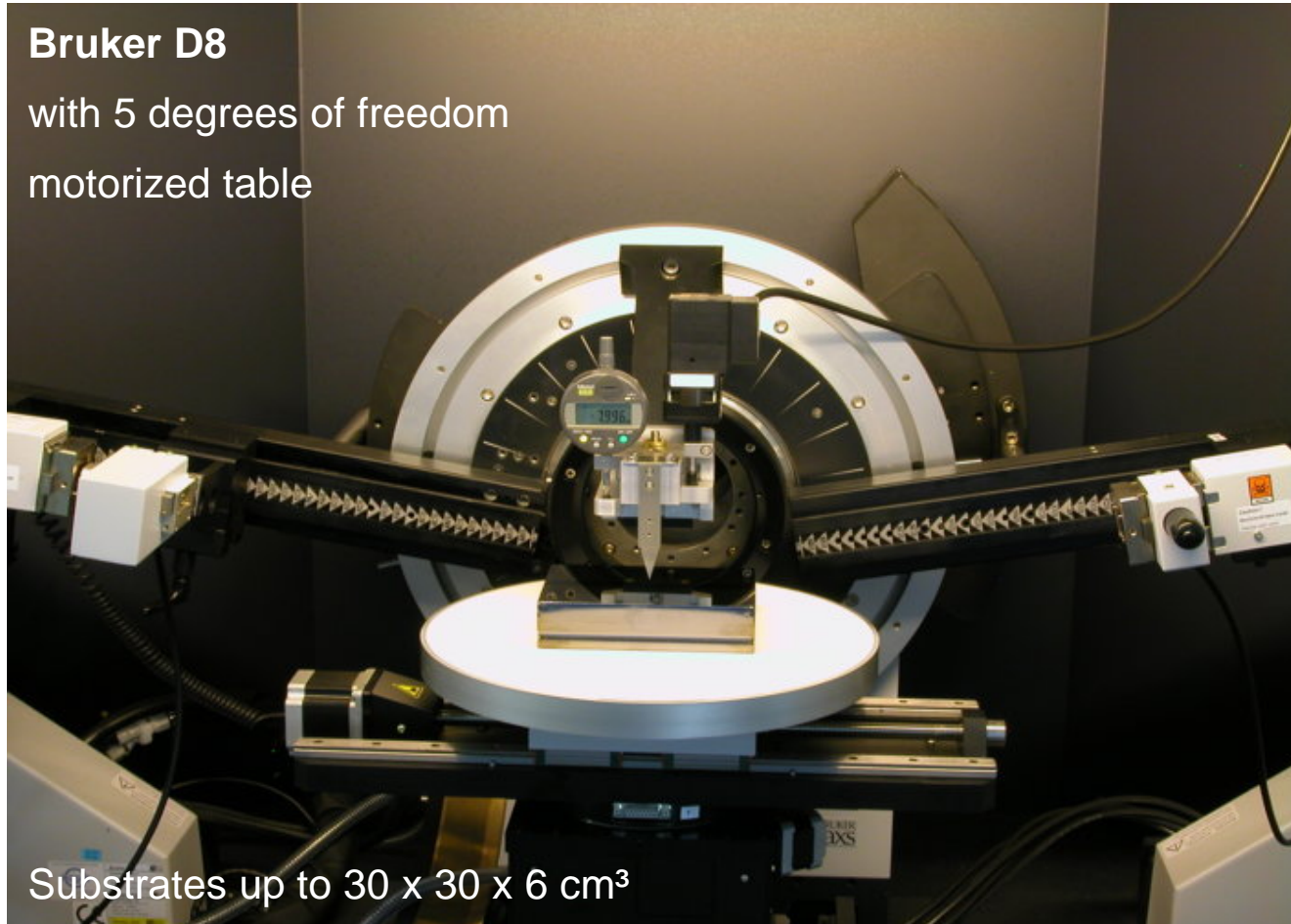


Perfect correspondence of the layer-thickness over 500 pairs

Standard process control: Characterization with X-Ray Reflectometry

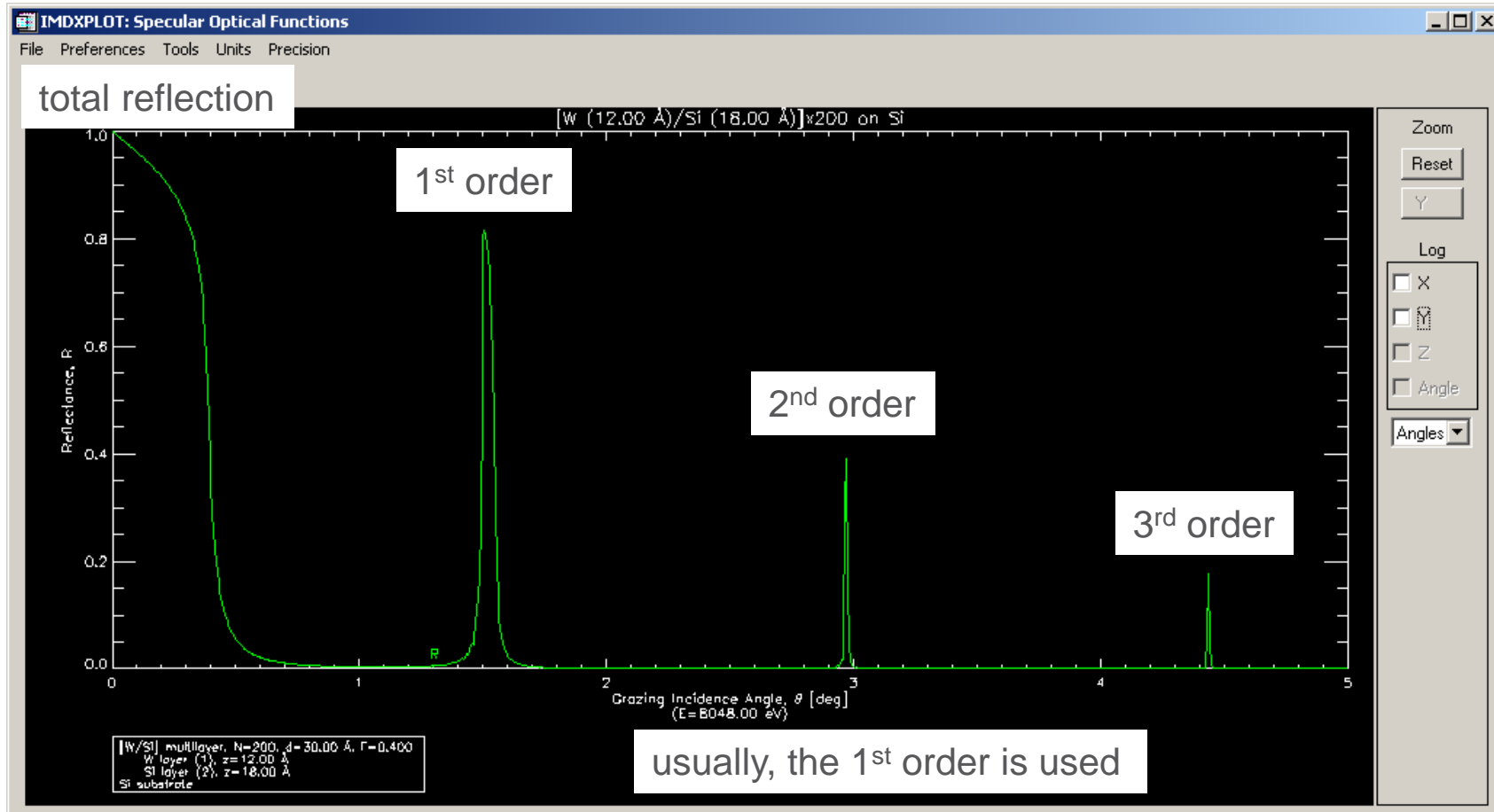
Bruker D8

with 5 degrees of freedom
motorized table



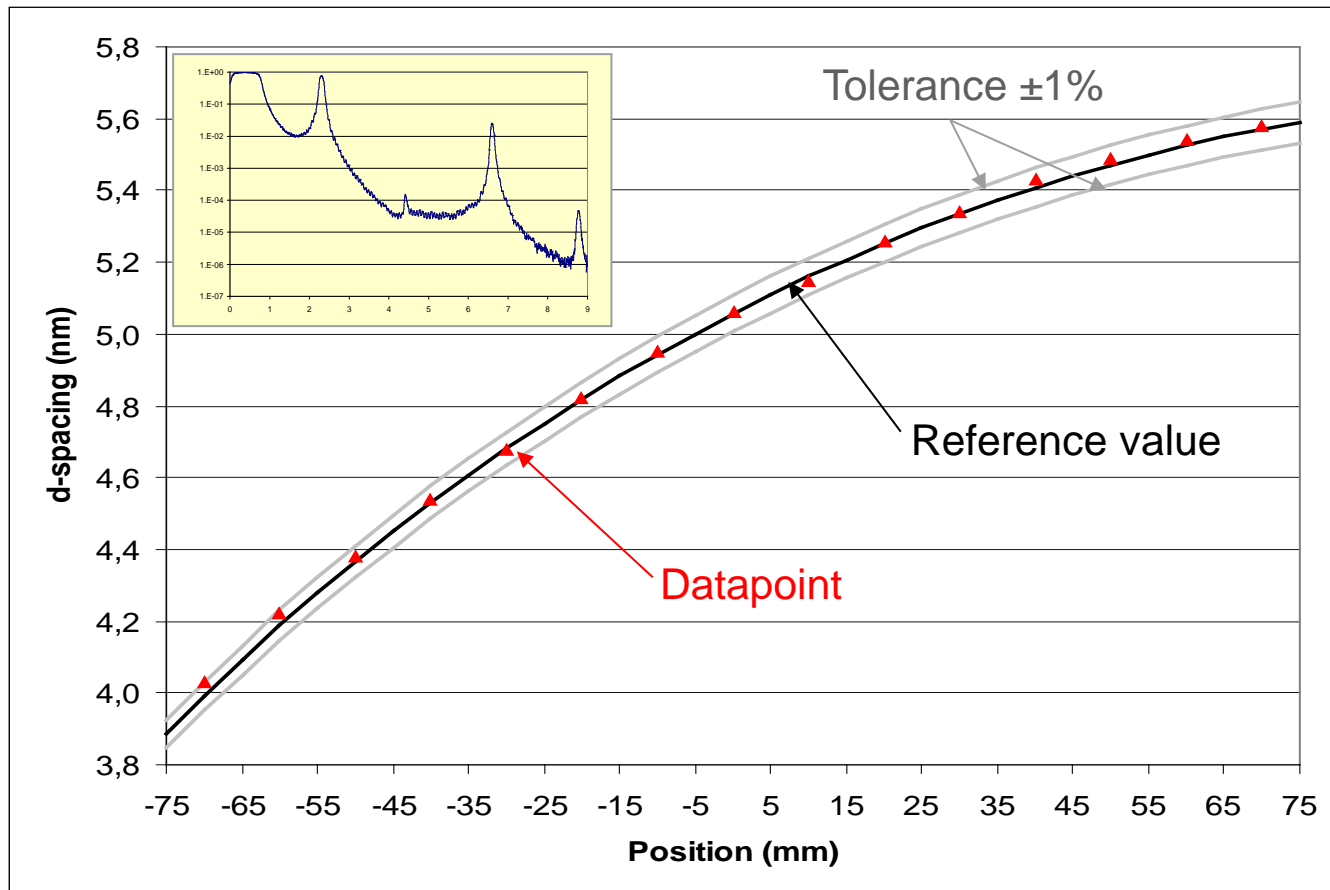
Substrates up to 30 x 30 x 6 cm³

Typical reflectivity curve at 8 keV (Cu K α)

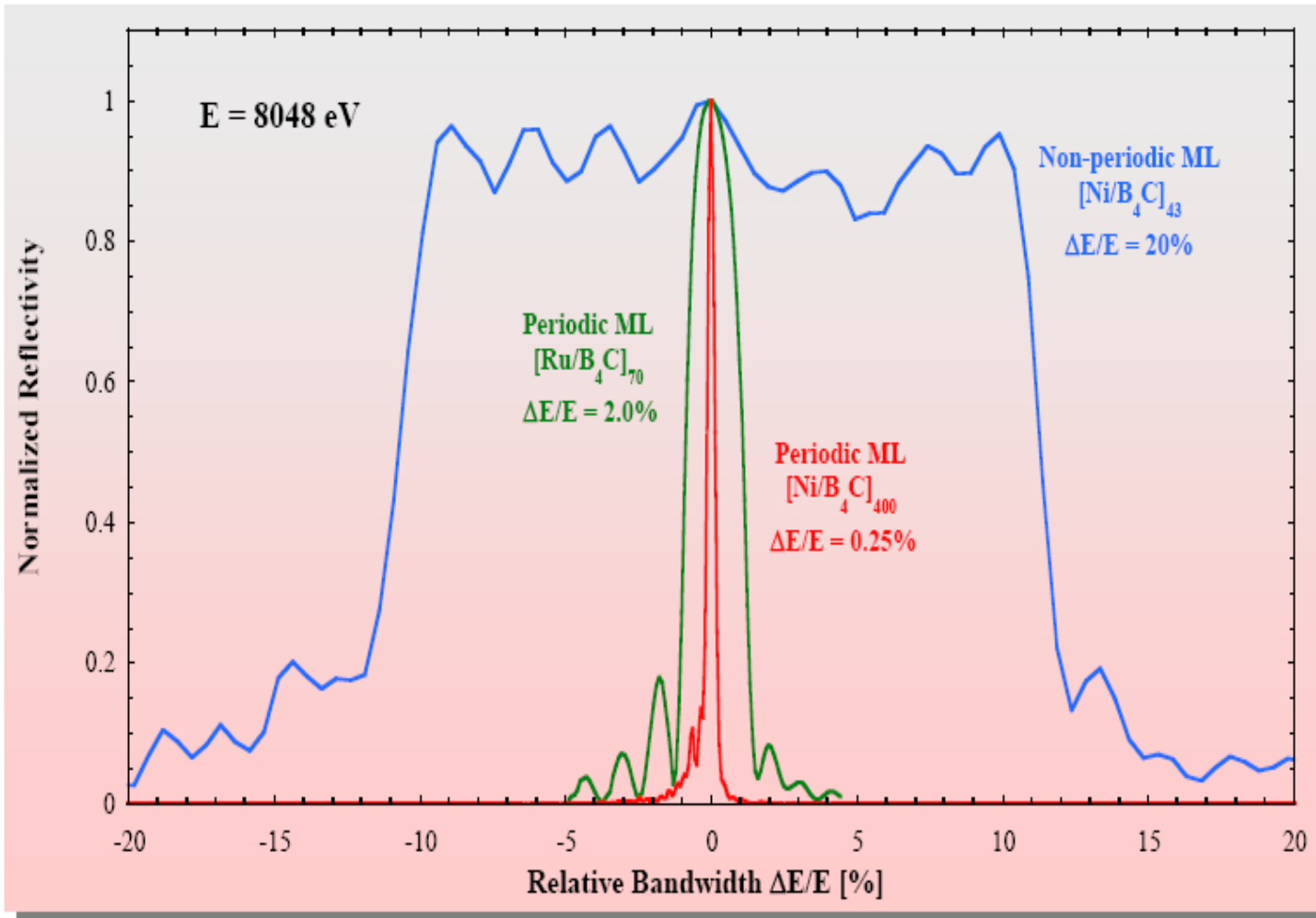


Reflectivity $R = 70 \dots 90 \%$, bandpass $\Delta E/E = 1 \dots 10\%$
→ Monochromatic beam (> 99% K α) with high flux

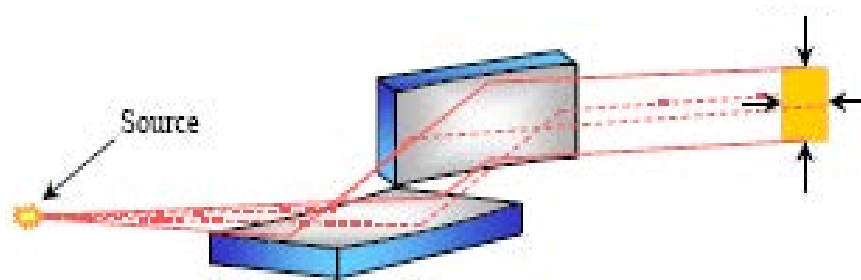
Graded Multilayer



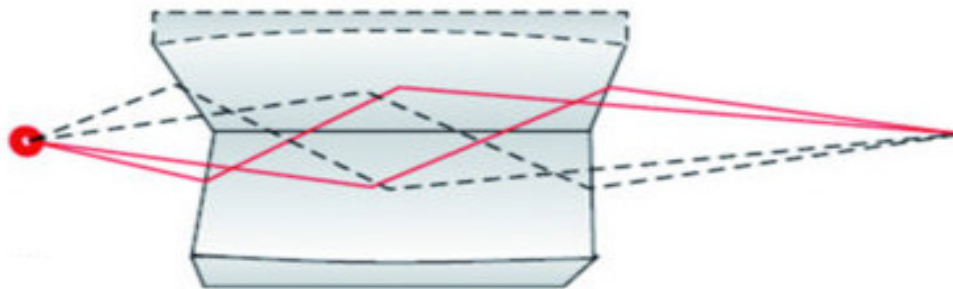
d-spacing accuracy better 1% !



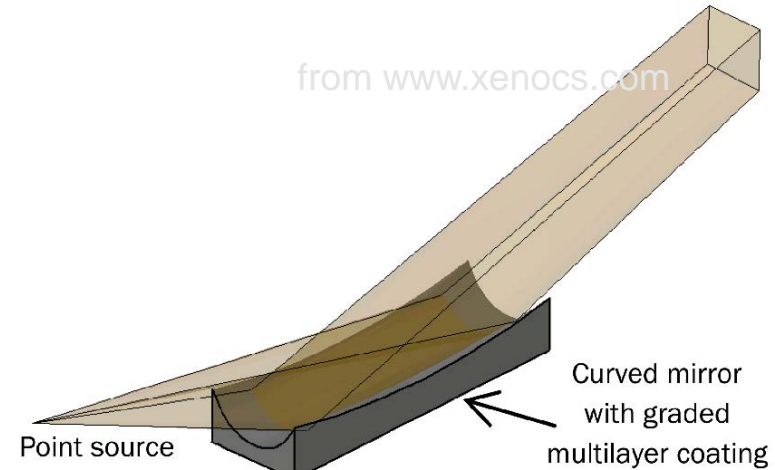
from C. Morawe, ESRF



KB (Kirkpatrick Baez) scheme, also called cross-coupled: two 1-dim optics; used at synchrotrons and few lab instruments

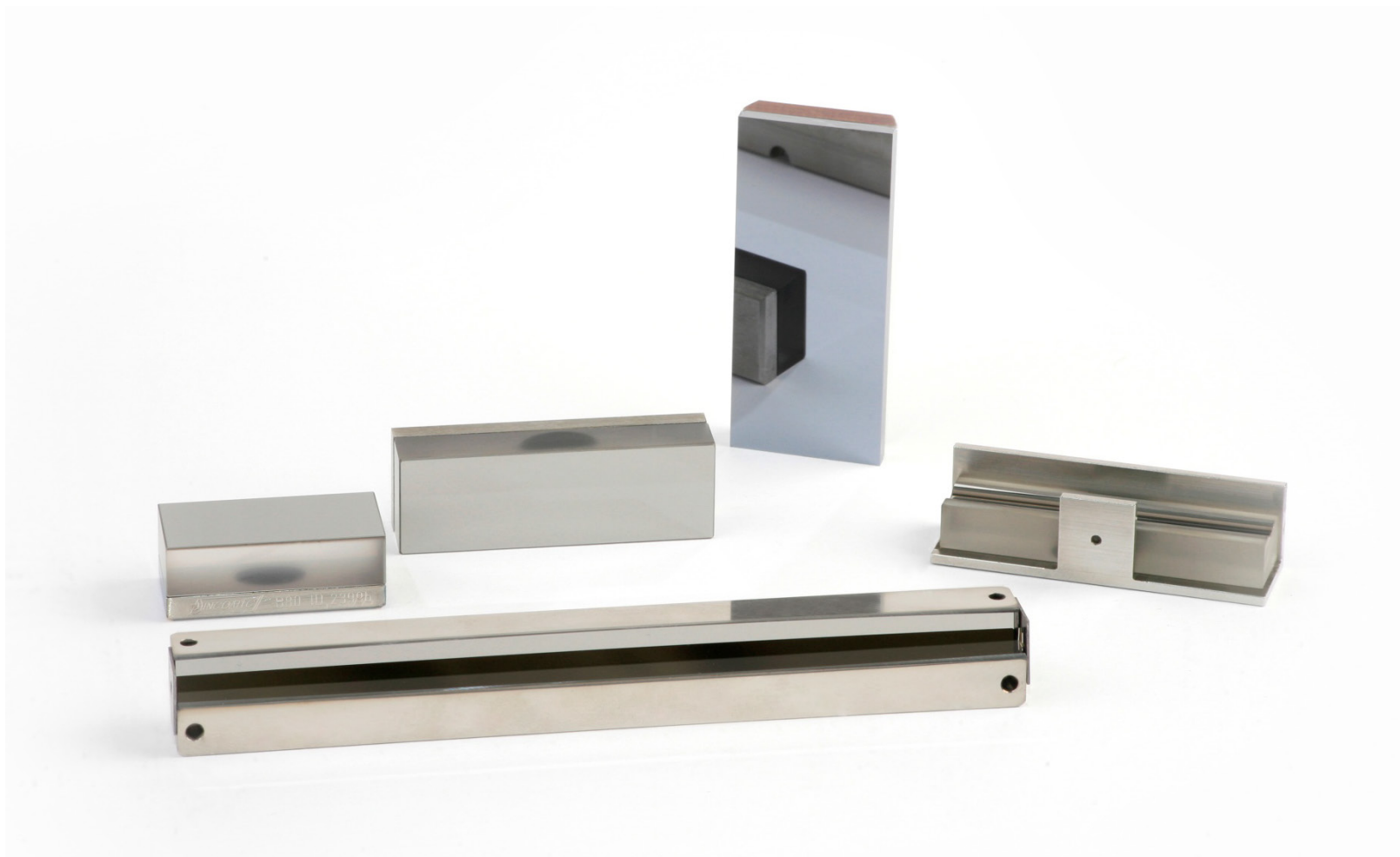


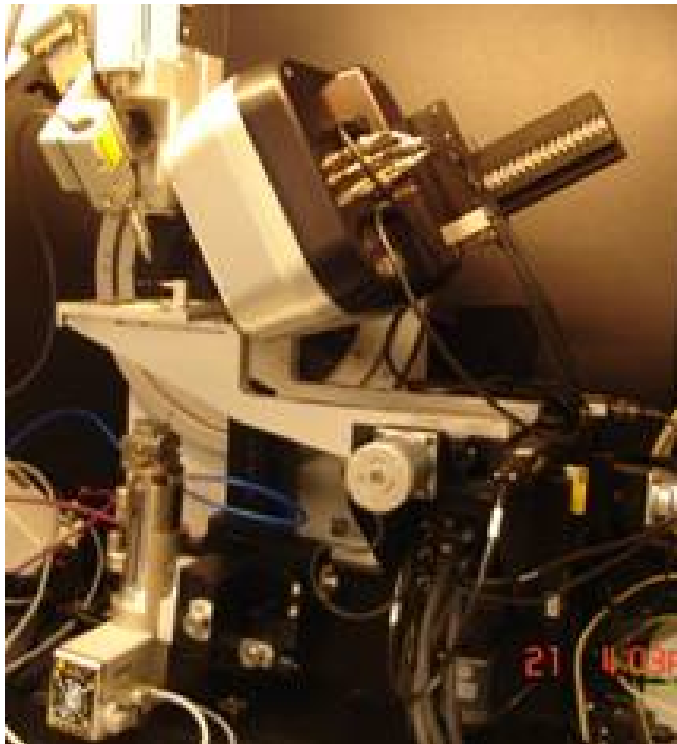
Side-by-side scheme, also called Montel Optics: two 1-dim optics mounted together; state-of-the-art in lab instruments



2-dim curved substrate:
Single-reflection Optics

**All concepts available for
focusing and collimating**



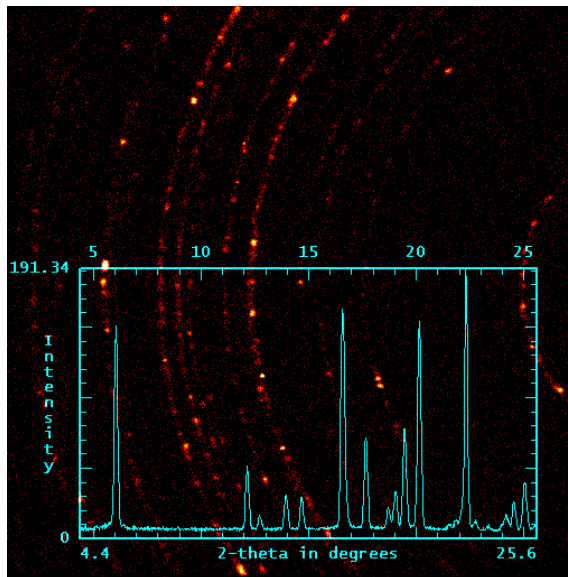


- measurements in transmission
- with Bruker D8 GADDS and VÅNTEC 2000
- Sample: Ibuprofene
- Sample-Detector distance: 290 mm

Sealed Tube

- 0.3 mm collimator
- cross-coupled mirrors

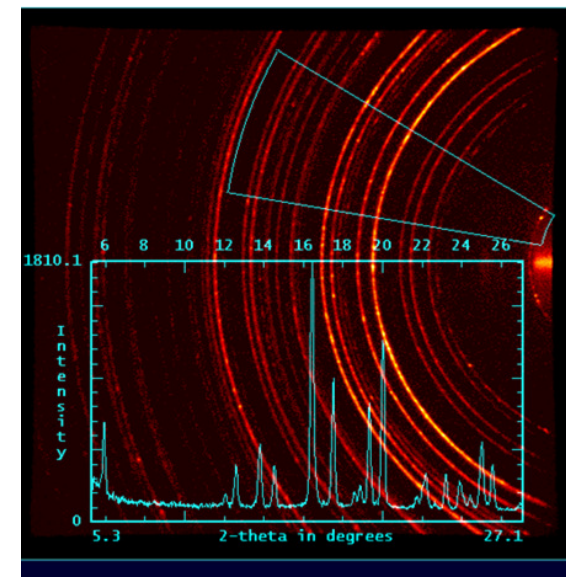
120 sec collection time

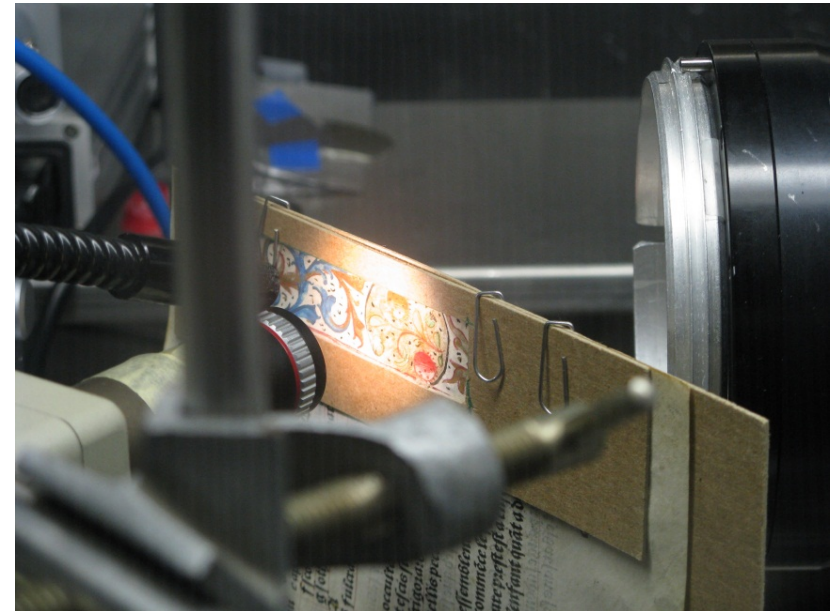
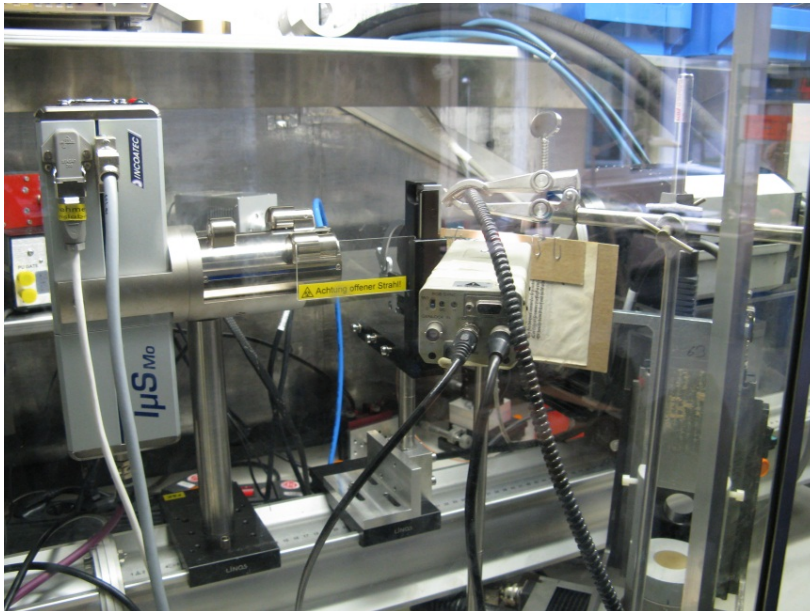


Microfocus source

- 0.3 mm snout
- Focussing 2-dim optics
- small slice for integration to obtain better resolution (poor detector calibration)

15 sec collection time

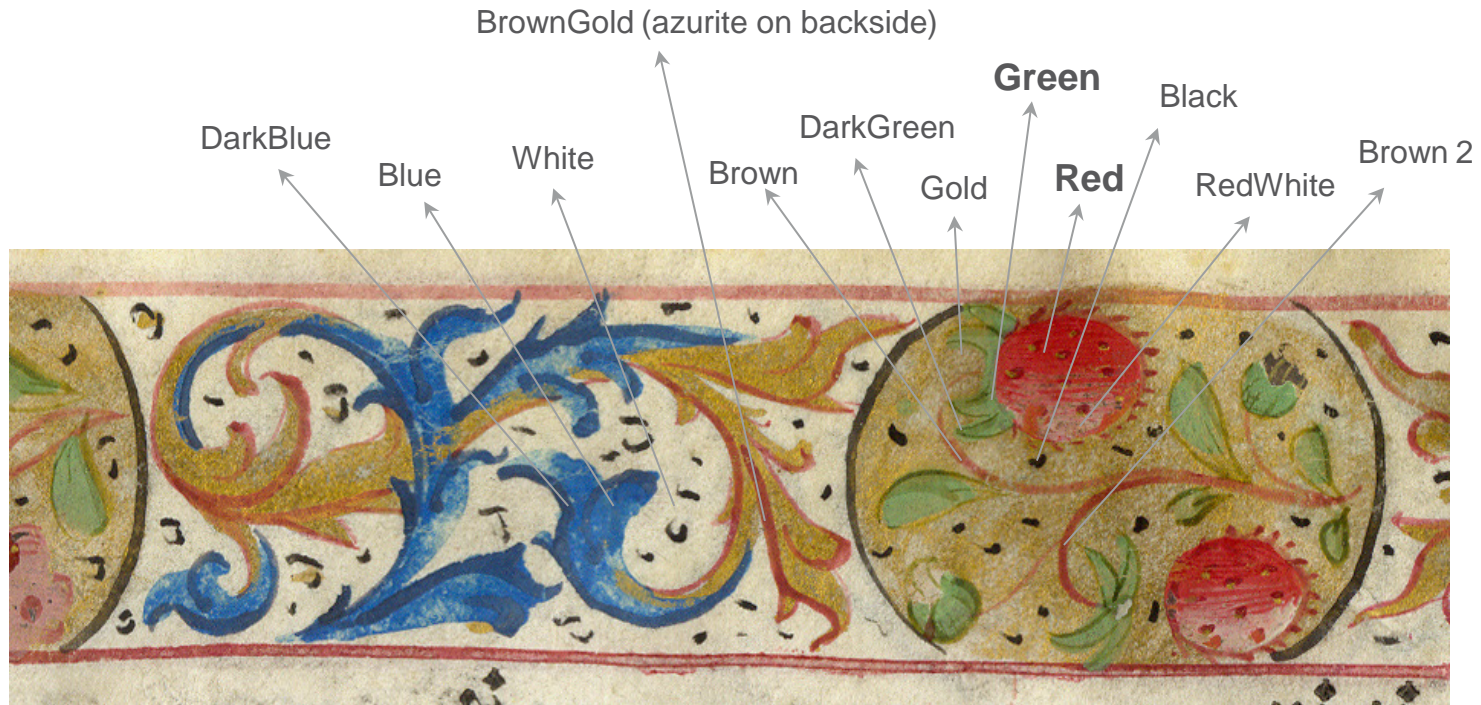




- Simultaneous XRD and XRF measurements
- Position sensitive measurements using focusing Mo-microfocus source
 - Resolution 150 μm

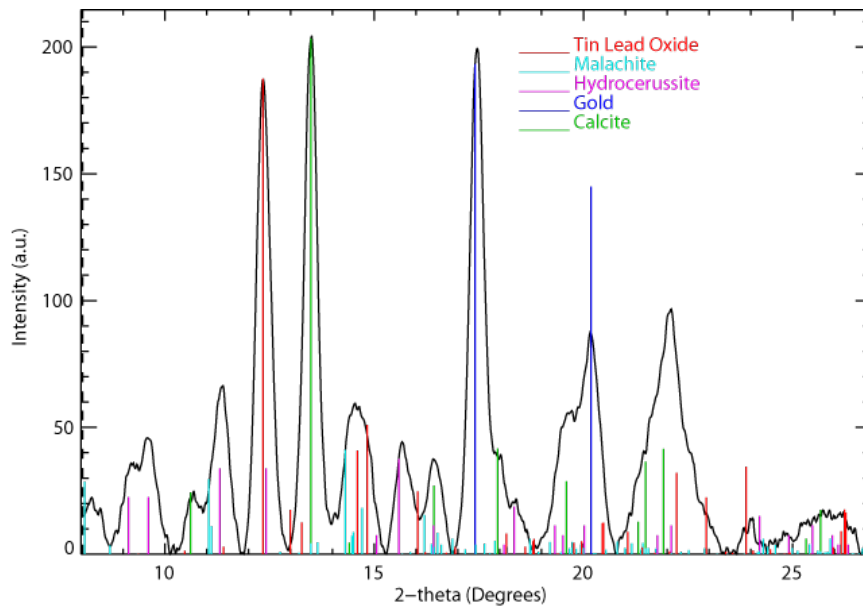
K. Janssens, Antwerpen

Illuminated Manuscript Point Measurements

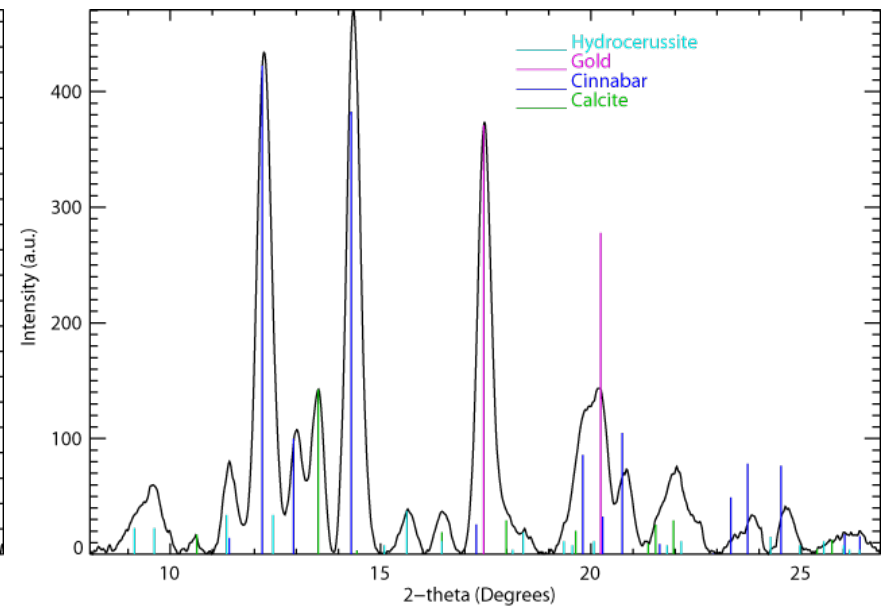


K. Janssens, Antwerpen

Green



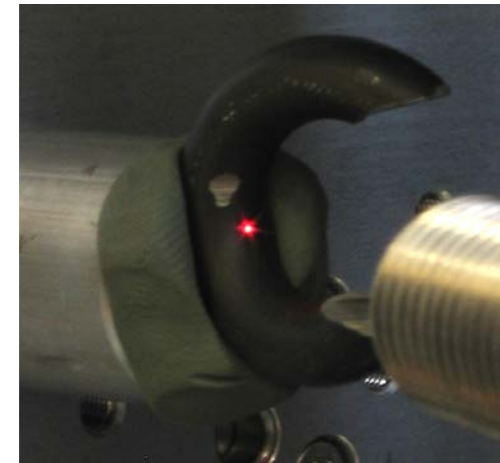
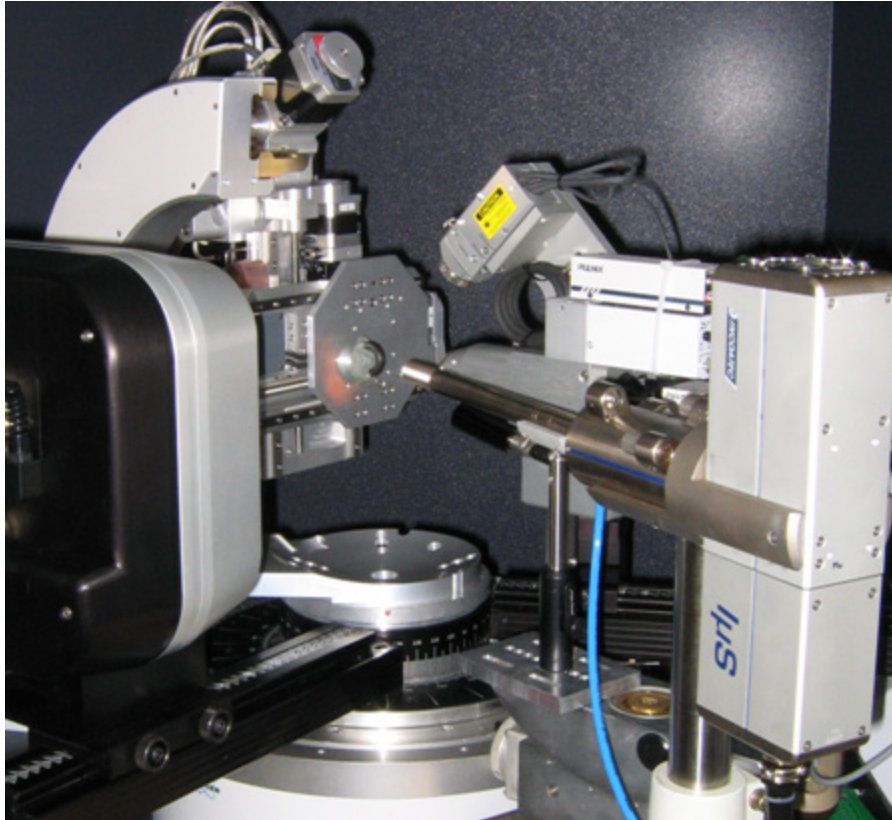
Red



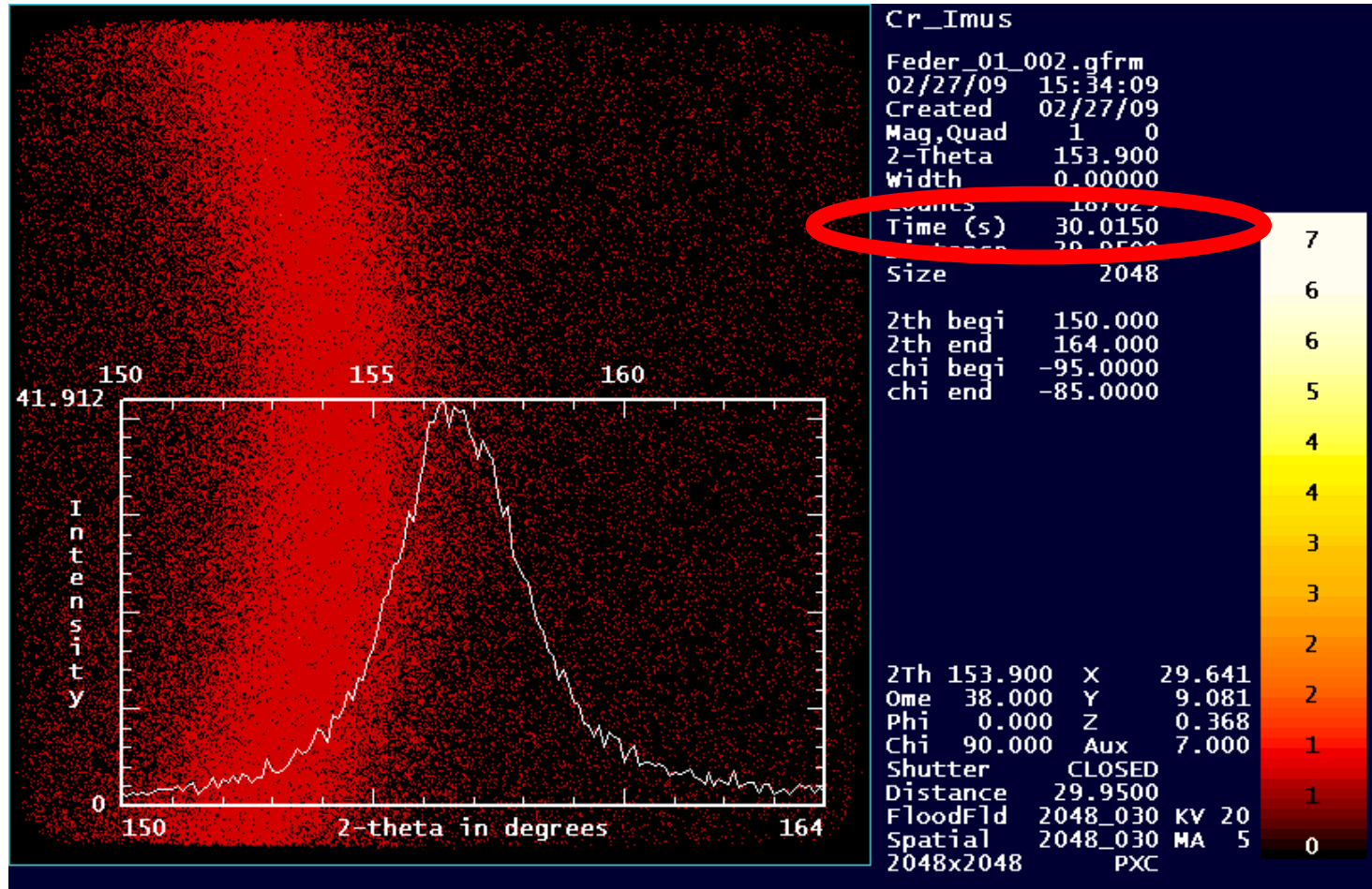
- Mo-microfocus source: 50 kV, 600 μ A, 30 sec exposure time
- Scanning Micro diffraction (combined with XRF):
4 x 4.5 mm², resolution 150 μ m, Total measurement time: 18 h
- Measurements and data evaluation by Frederick Vanmeert

K. Janssens, Antwerpen

Fast Stress Analysis: Steel Spring



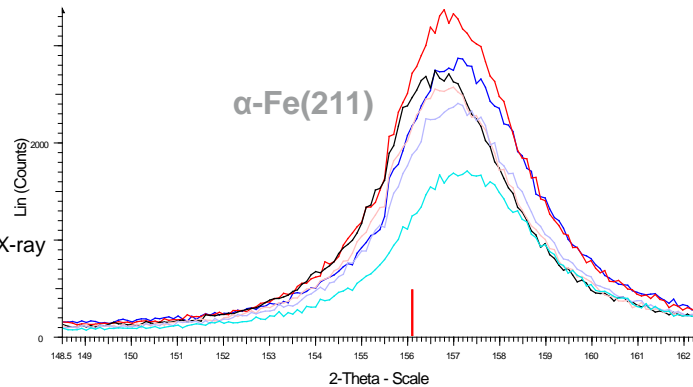
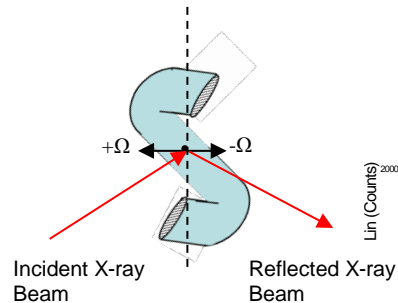
H. and U. Göbel, LabXA and M. Schuster, Siemens, Munich



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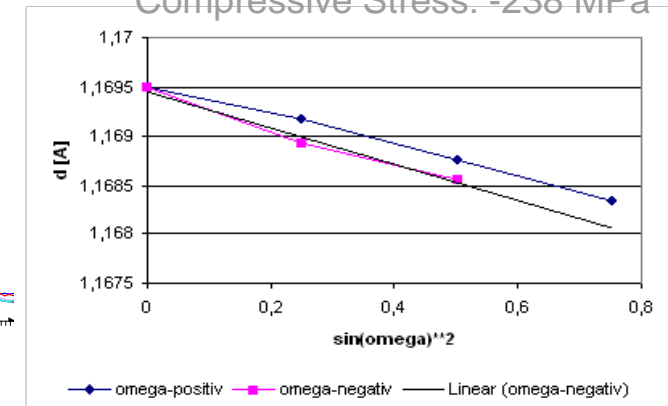
Steel Spring: Results – Tensile and compressive stress at the inner surface

Inner Surface of Spring, +45°-Direction

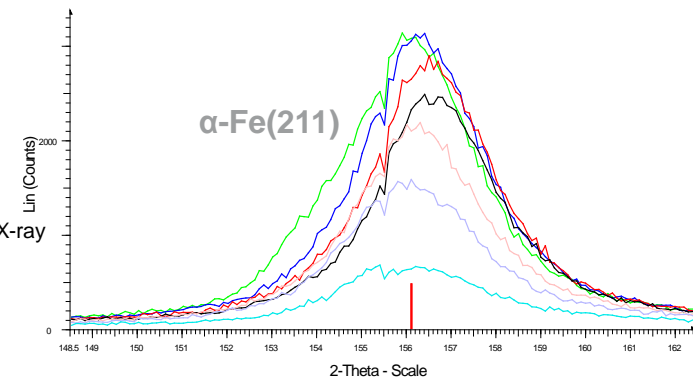
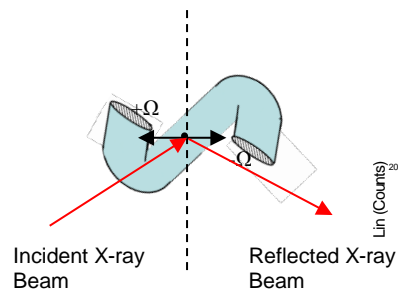


File: I45_45.RAW - innen p=45 o=45 - WL1: 2.2897 - WL2: 2.293
 File: I45_30.RAW - innen p=45 o=30 - WL1: 2.2897 - WL2: 2.293
 File: I450.RAW - innen p=45 o=0 - WL1: 2.2897 - WL2: 2.29361
 File: I450.RAW - innen p=45 o=30 - WL1: 2.2897 - WL2: 2.29361
 File: I450.RAW - innen p=45 o=45 - WL1: 2.2897 - WL2: 2.29361
 File: I4560.RAW - innen p=45 o=60 - WL1: 2.2897 - WL2: 2.29361
 06-0696 (*) - Iron, syn - Fe - Cubic - a 2.86640 - b 2.86640 - c 2.86

Compressive Stress: -238 MPa

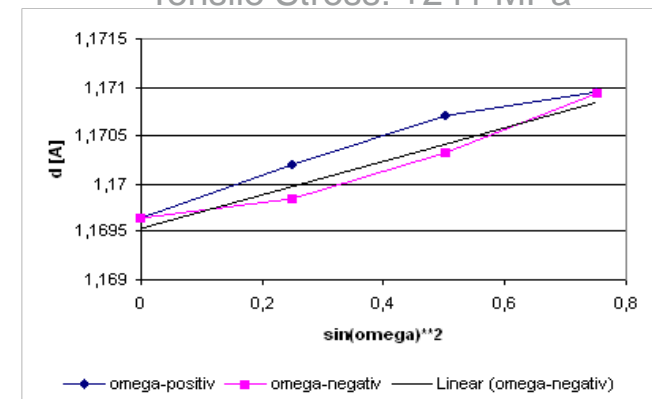


Inner Surface of Spring, -45°-Direction



File: L_45_60.RAW - innen p=45 o=60 - WL1: 2.2897 - WL2: 2.29
 File: L_45_45.RAW - innen p=45 o=45 - WL1: 2.2897 - WL2: 2.29
 File: L_45_30.RAW - innen p=45 o=30 - WL1: 2.2897 - WL2: 2.29
 File: L_450.RAW - innen p=45 o=0 - WL1: 2.2897 - WL2: 2.29361
 File: L_450.RAW - innen p=45 o=30 - WL1: 2.2897 - WL2: 2.29361
 File: L_450.RAW - innen p=45 o=45 - WL1: 2.2897 - WL2: 2.29361
 File: L_4560.RAW - innen p=45 o=60 - WL1: 2.2897 - WL2: 2.29361
 06-0696 (*) - Iron, syn - Fe - Cubic - a 2.86640 - b 2.86640 - c 2.86

Tensile Stress: +241 MPa



H. and U. Göbel, LabXA and M. Schuster, Siemens, Munich

- Multilayer mirrors for a variety of energies: Cr, Mn, Fe, Co, Cu, Ge, Mo, Ag, and higher energies for synchrotrons
- Large variety of possible material combinations
- Multilayers are stable (except against ozone)

New sources with (sub-) micrometer beams:

- microfocus sources
- liquid metal jet sources
- synchrotron beam lines

Energy range 5 keV to 100 keV

Requirement: Pre-figured substrates with a very low figure error for very small spots of focusing mirrors and very homogeneous spots of collimating mirrors

H. Göbel, U. Hermeking-Göbel, LabXA, Munich

M. Schuster, Siemens, Munich

K. Janssens, F. Vanmeert, Antwerpen

All People from Bruker and Incoatec

Thank You

Please contact for more information

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